

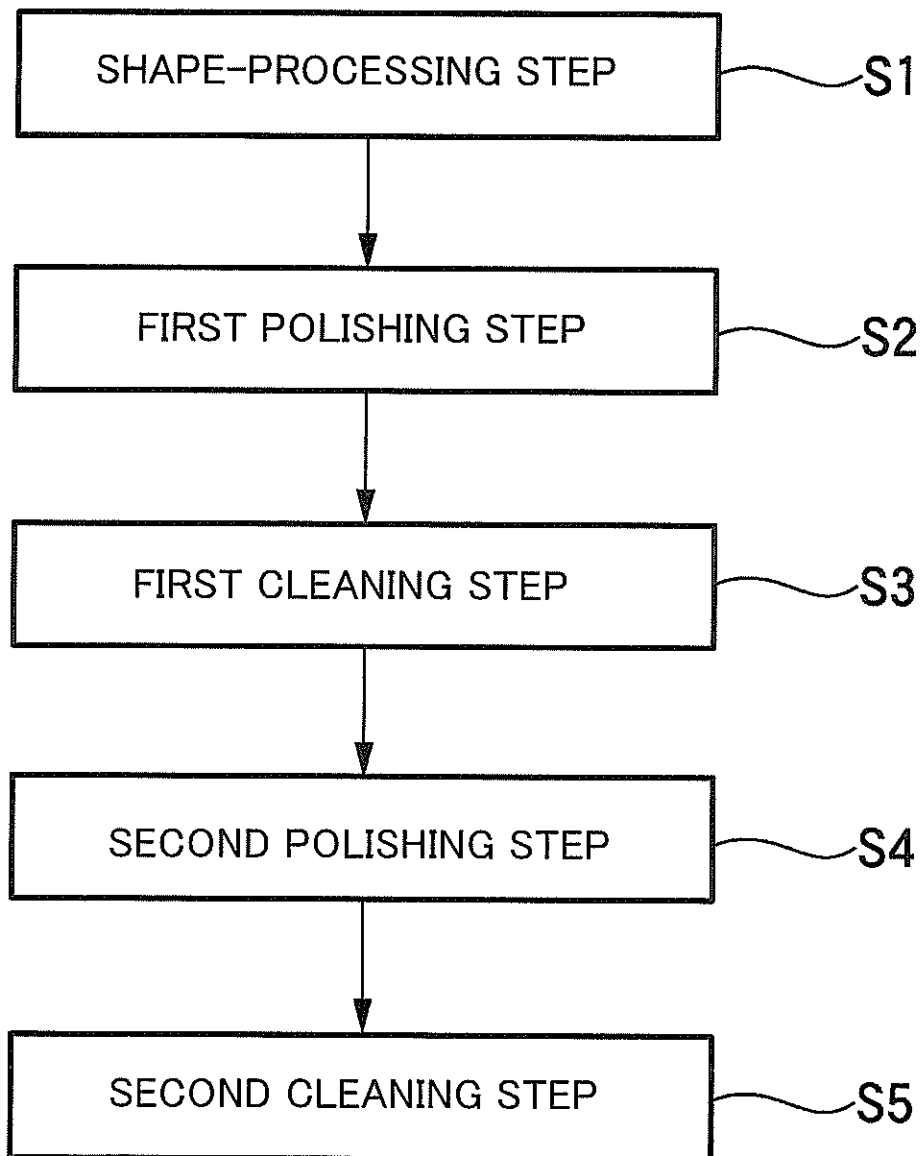
Fig. 1

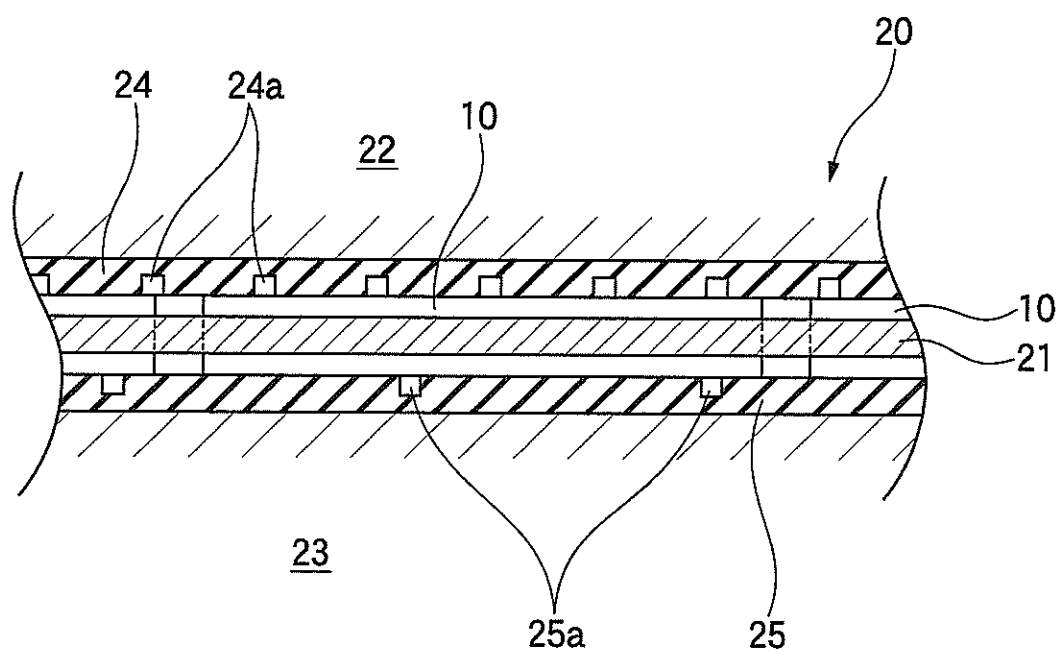
Fig. 2

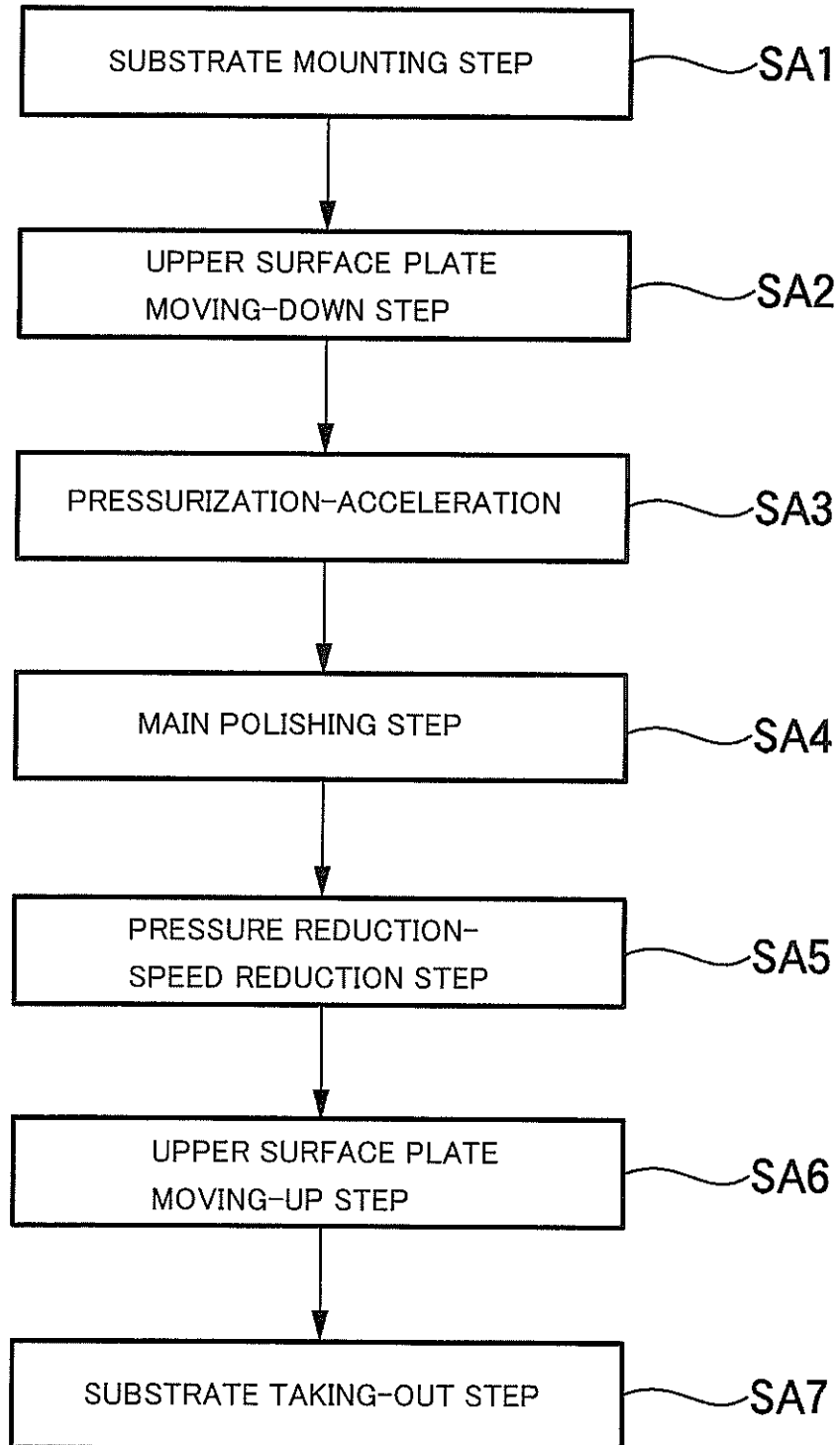
Fig. 3

Fig. 4

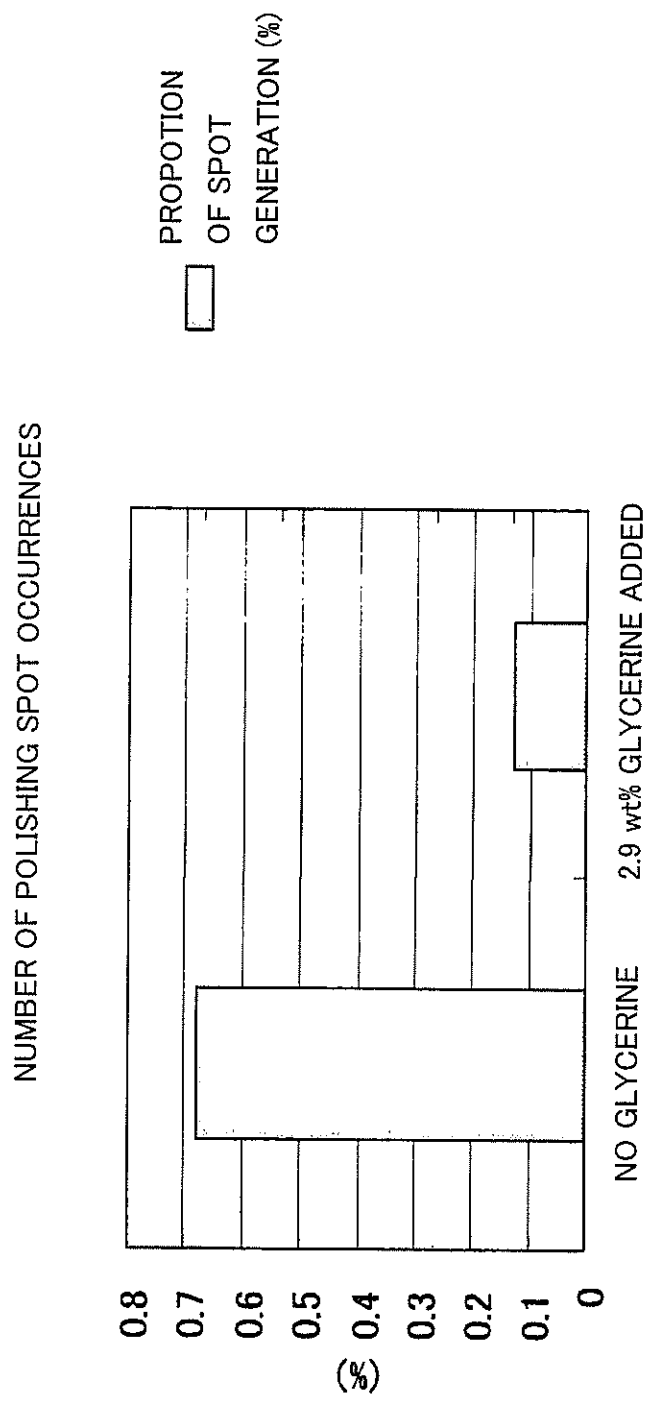
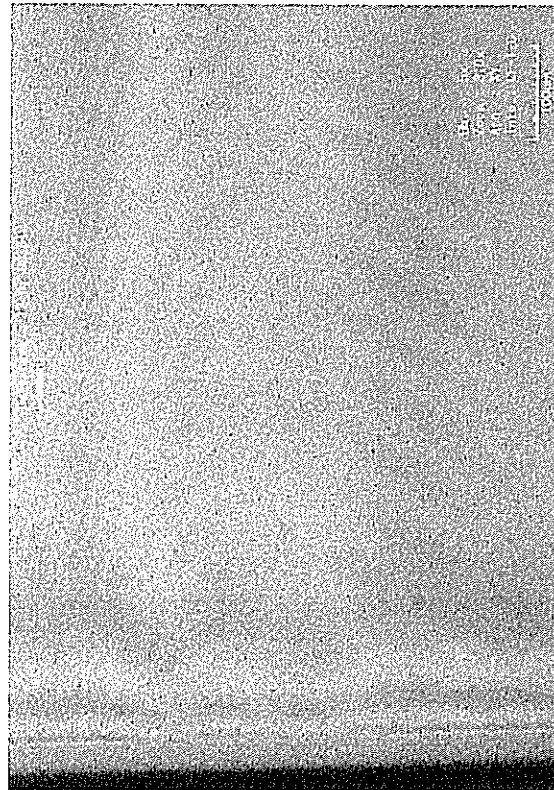


Fig. 5

(a)

CERIUM OXIDE



(b)

COLLOIDAL SILICA

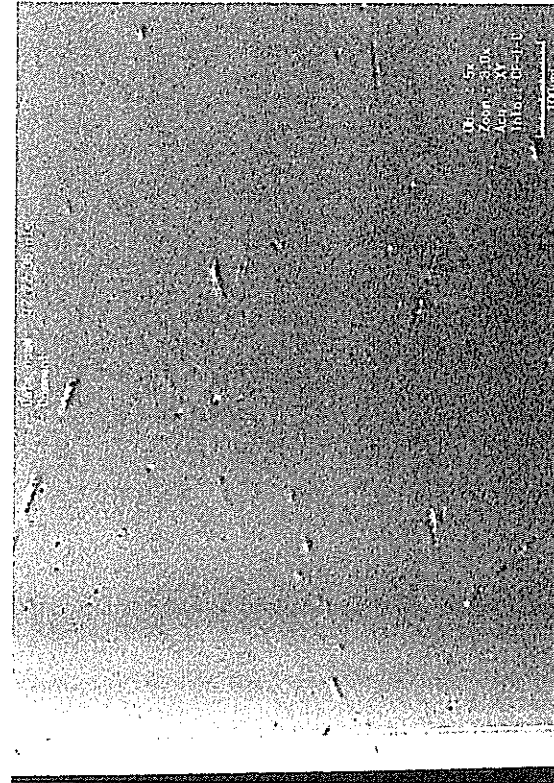


Fig. 6

POLISHING CONDITIONS	FREQUENCY OF DAMAGE GENERATION (damages/disk)
CERIUM OXIDE	0
COLLOIDAL SILICA	1,020

Fig. 7

POLISHING CONDITIONS	FREQUENCY OF DAMAGE GENERATION
NO GLYCERINE ADDED	8.6% (3,001 SUBSTRATES / 34,905 SUBSTRATES)
0.8 wt% GLYCERINE ADDED	2.2% (308 SUBSTRATES / 14,019 SUBSTRATES)
2.9 wt% GLYCERINE ADDED	2.7% (3,026 SUBSTRATES / 112,080 SUBSTRATES)

Fig. 8

EXAMINATION CONDITIONS	COEFFICIENT OF FRICTION
NO ADDITIVE ADDED	0.15
2.9 wt% GLYCERINE ADDED	0.12
2.9 wt% ETHYLENE GLYCERINE ADDED	0.12

Fig. 9

POLISHING CONDITIONS	POLISHING RATE (/ min / one side)
NO ADDITIVE ADDED	32 nm
2.9 wt% GLYCERINE ADDED	32 nm
5 wt% GLYCERINE ADDED	18 nm
10 wt% GLYCERINE ADDED	13 nm

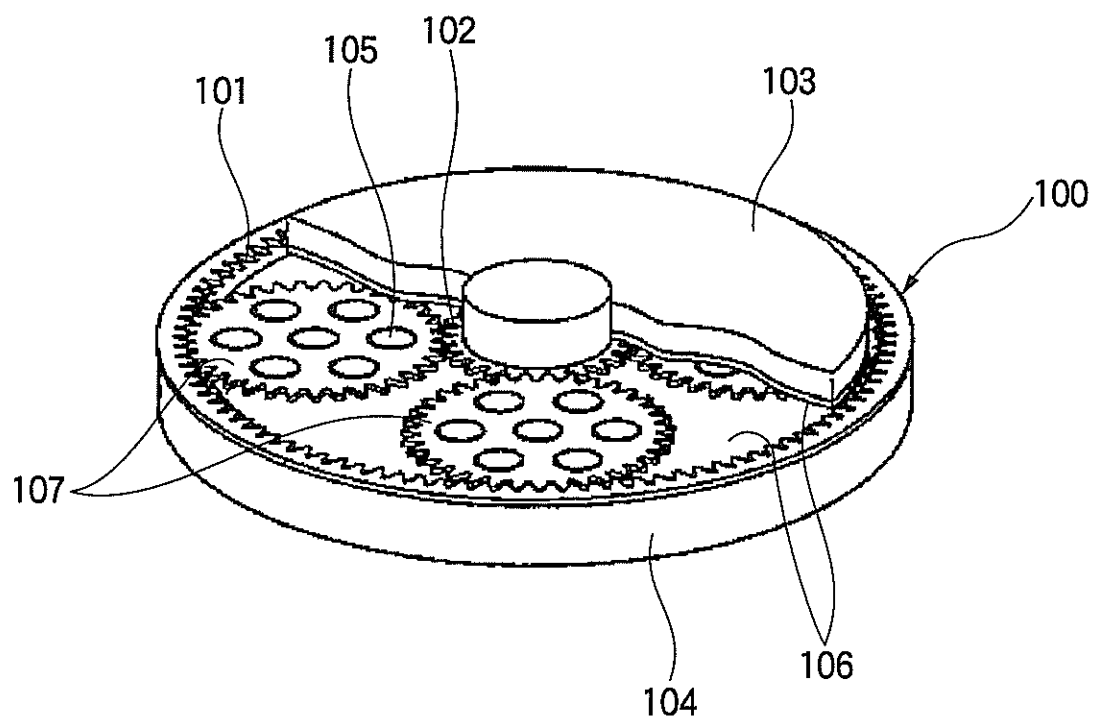
Fig. 10

Fig. 11